## ${f Q}$ uantum impurities and resultant two-channel Kondo problem in ${f ZrAs}_{1.58}{f Se}_{0.39}$

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Low-*T* electrical resistivity  $\rho(T)$  of the closely related phases  $\operatorname{ZrAs}_{1.58}\operatorname{Se}_{0.39}$  (3% of vacancies within the monoatomic As layers) and  $\operatorname{ZrP}_{1.54}\operatorname{S}_{0.46}$  (the 2*a* site fully occupied with P atoms) has been investigated along the *c* axis down to  $T \geq 0.08$  K and in  $B \leq 14$  T. Whereas for both systems a  $-AT^{1/2}$  term in  $\rho(T)$  was observed below  $T \approx 15$  K, their response to the magnetic field was found to be qualitatively different: for the As-based compound, a coefficient  $A (= 0.167 \ \mu\Omega \mathrm{cmK}^{-1/2})$  remains virtually unchanged even in the highest available magnetic fields. For the P-based compound, however, the *A*-coefficient value is linearly reduced from 0.038 to 0.008  $\mu\Omega \mathrm{cmK}^{-1/2}$  with increasing *B* up to 14 T, *i.e.*, by factor nearly 5. These distinctly different observations indicate qualitatively different phenomena occurring in the material with (ZrAs\_{1.58}Se\_{0.39}) and without (ZrP\_{1.54}S\_{0.46}) broken pnictogen-pnictogen chemical bonds: a  $\rho(T, B)$  behavior of the latter system is characteristic for the 3D electron-electron interactions, while the *B*-independent  $-AT^{1/2}$  term points at a two-channel Kondo problem derived from two-level states triggered by non-magnetic quantum impurities in the As layers. R. Niewa *et al.*, J. Solid State Chem. **183**, 1309 (2010).